

## Nucleation – Concept of Surface Energy

Differential Energy  $dE$  cost for creating a surface are  $dA$

$$dE = TdS - PdV + \gamma dA$$

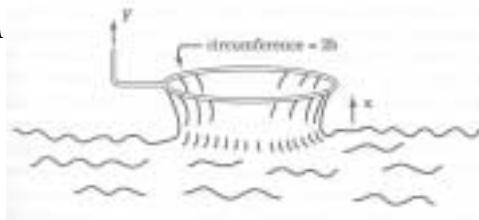
$$dG = -SdT + VdP + \gamma dA$$

$$dG = \gamma dA$$

$$dE = \delta W = \gamma dA$$

$$Fdx = \gamma dA = \gamma(2b)dx$$

$$\gamma = \frac{F}{2b}$$



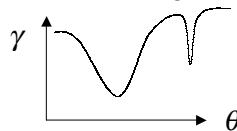
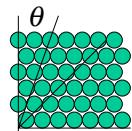
Force per unit length of the circumference (N/m) is the surface tension and in case of the liquids surface energy per unit area (J/m<sup>2</sup>) is the same as the surface tension

## Physical understanding of the origin of surface energy

- Why is there a surface energy associated with solid surfaces?
- What is the physical explanation/interpretation?
- No bonds from the top. Compared to bulk the bonding may not be satisfied.
- Surface energy tries to minimize itself by diffusion. If surface diffusion is fast the nuclei will expose the lowest energy surfaces.
- $\gamma$  depends on
  - ⇒ Chemical composition
  - ⇒ Atomic scale roughness
  - ⇒ Atomic scale reconstruction
  - ⇒ Crystallographic orientation
- Example: (111) plane of an FCC structure is the closest pack plane. The # of bonds in the plane is maximized and the number out of the plane are minimized. Consequently  $\gamma_{fcc}^{111} < \gamma_{fcc}^{100}$

## Physical understanding of the origin of surface energy

- Charge neutrality @ the surface leads to lower  $\gamma$ .
- In crystals having ionic bonds (NaCl, CaF<sub>2</sub>) or polar bonds (GaAs, ZnO)  $\gamma$  tends to be lower for faces that contain equal numbers of cations (Na, Ca, Ga, Zn) and anions (Cl, F, As, O).
- i.e., nonpolar surfaces are lower energy.
- $\gamma$  for a particular surface may be lower than predicted from the dangling bond density because crystal surfaces rearrange (called reconstruction) such that termination does not necessarily have the geometry of the atomic arrangements of the cleaved plane in the bulk crystal.
- $\gamma$  is lower for low index planes called singular surfaces



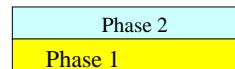
## Nucleation

Phase 3



or

Phase 3



At constant P and T  $dG < 0$  for nucleation to occur

create area  $dA$  of 1-2 and 2-3 interface

Phase 2  
Phase 1

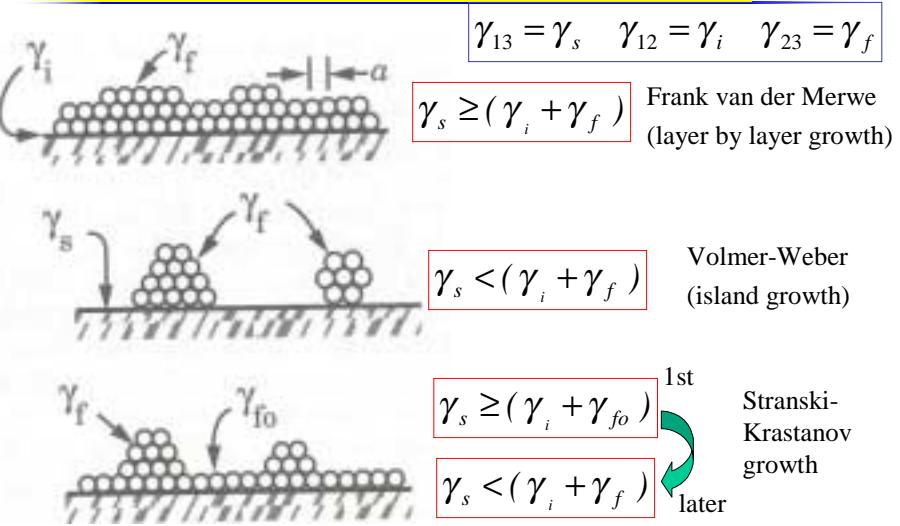
Phase 3

$$G_{\text{before}} - G_{\text{after}} = [\gamma_{13} - (\gamma_{12} + \gamma_{23})]dA$$

$$[\gamma_{13} - (\gamma_{12} + \gamma_{23})] \geq 0 \rightarrow \text{Phase 2 spreads over phase 1 completely "wetting" it}$$

$$[\gamma_{13} - (\gamma_{12} + \gamma_{23})] < 0 \rightarrow \text{Phase 2 remains in a lens configuration}$$

## Film Growth Modes

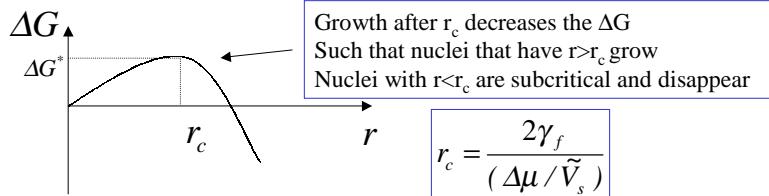


## Nucleation: the critical radius

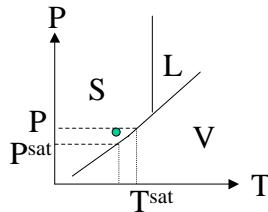
Assume that  $\gamma_s < (\gamma_i + \gamma_f)$

$$\Delta G = (\mu^s - \mu^v) \frac{1}{V_s} \frac{4}{3} \pi r^3 + \gamma_f 4\pi r^2$$

$$\Delta G = -\Delta\mu \frac{1}{V_s} \frac{4}{3} \pi r^3 + \gamma_f 4\pi r^2 \quad \text{where} \quad \Delta\mu = \mu^v - \mu^s$$



## Nucleation rate



$$\Delta G^* = \frac{16}{3} \frac{\pi \gamma_f^3}{(\Delta \mu / \tilde{V}_s)^2}$$

$$\Delta \mu = \mu^v - \mu^s$$

$$\mu^v = \mu^o(P^o, T) + RT \ln(P / P^o)$$

$$at \quad P = P^{sat} \quad \mu^s = \mu^v = \mu^o(P^o, T) + RT \ln(P^{sat} / P^o)$$

$$\Delta \mu = RT \ln(P / P^{sat})$$

$$\Delta G^* = \frac{16}{3} \frac{\pi \gamma_f^3}{\left\{ \frac{RT \ln(P / P^{sat})}{\tilde{V}_s} \right\}^2}$$

Another way of looking at it

$$\Delta \mu \propto \Delta T$$

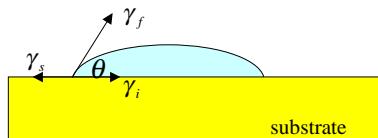
$$r_c \propto \frac{2\gamma_f}{\Delta T}$$

$$\Delta G^* \propto \frac{\gamma_f^3}{(\Delta T)^2}$$

Nucleation rate

$$R_n \propto e^{-\Delta G^* / RT}$$

## Nucleation morphology



Assuming amorphous or liquid nuclei one can do a force balance in the direction parallel to the surface

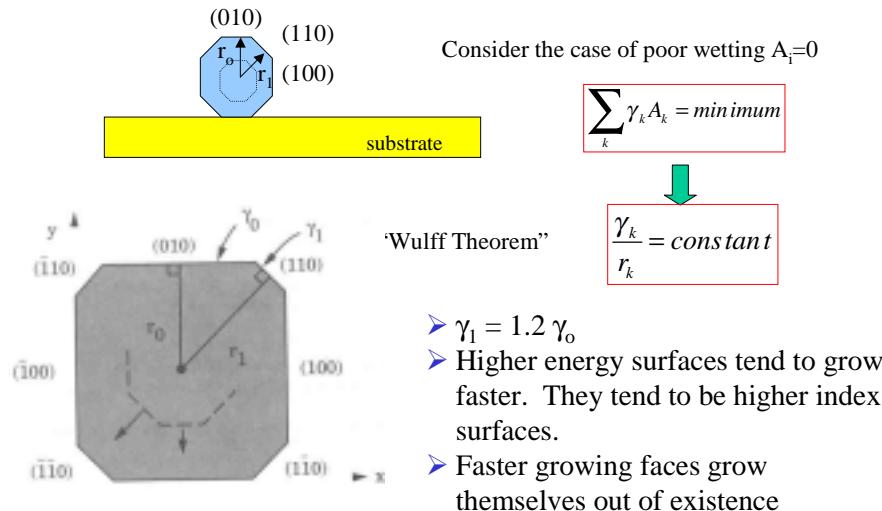
$$\gamma_s = \gamma_i + \gamma_f \cos \theta$$

While we can equate surface energy with surface tension in liquids this is not the case with solids. For solids there is also a quantity called surface stress.

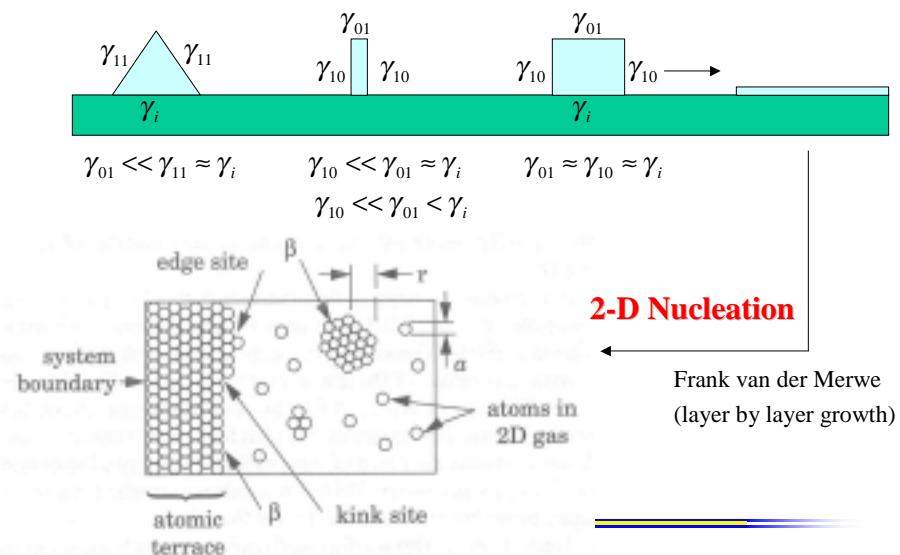
In solids surface energy is anisotropic and the shape of the nuclei will adjust to minimize the energy of the total surface area through

$$\sum_k \gamma_k A_k = \text{minimum}$$

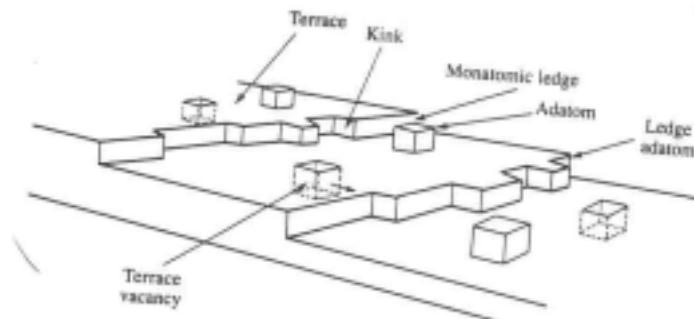
## Nucleation morphology



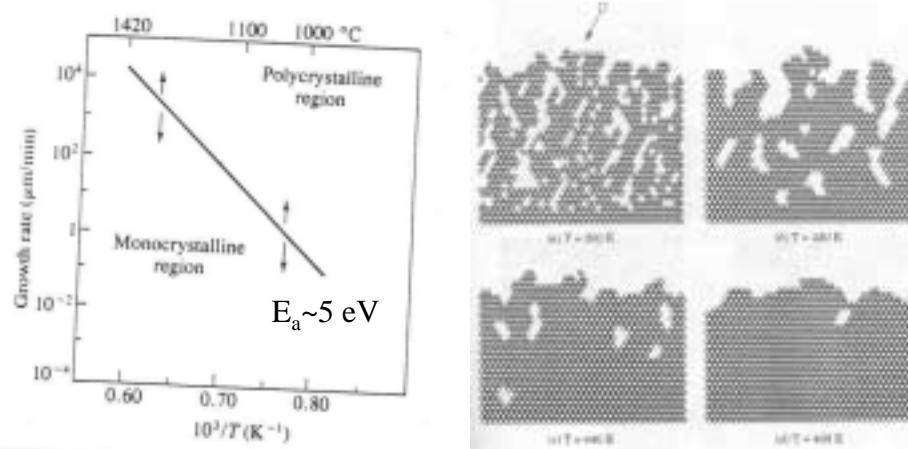
## Island Nucleation & 2-D nucleation



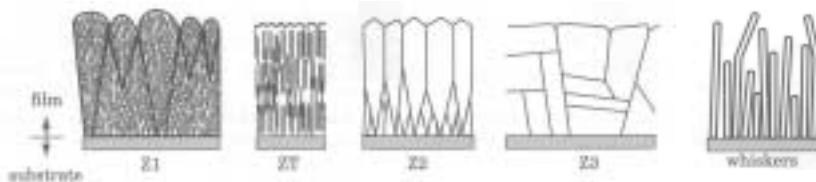
## Epitaxy



## Film crystallinity



## Film Morphology - Growth Zones



- **Z1:**  $T_s/T_m$  so low that surface diffusion is negligible ( $\Lambda < a$ ). ~10 nm columns (poor crystallinity or amorphous) separated by ~1-2 nm voids. Columns terminate in domes at the top
- **ZT:** like Z1 but domes and voids are absent. Common in energy-enhanced deposition methods (plasma, sputtering, etc.)
- **Z2:** occurs for  $T_s/T_m > 0.3$ , surface diffusion is significant, Tight columns with grain boundaries, column diameter  $\uparrow$  with  $T_s \uparrow$ . Columns less defected than Z1 or ZT and faceted at top. The boundaries are planes of reduced bonding rather than planes of xtallographic discontinuity.
- **Z3:** occurs for  $T_s/T_m > 0.5$ , significant bulk annealing takes place, isotropic and equiaxed xtals. Films are smoother.